

Notice of References Cited	Application/Control No. 10/810,645	Applicant(s)/Patent Under Reexamination KER ET AL.	
	Examiner Jeff Natalini	Art Unit 2858	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-5,519,327	05-1996	Consiglio, Rosario J.	324/678
	C	US-4,823,088	04-1989	Fukuda, Yasuhiro	324/456
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	E	US-6,541,981	04-2003	Allard et al.	324/458
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	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Chen et al. "Investigation of the Gate-Driven Effect and Substrate Triggered Effect on ESD Robustness of CMOS Devices" December 2002, IEEE Transactions on Device and Materials Reliability. Vol 1, No. 4; pgs 190-203.
	V	Barth et al. "TLP Calibration, Correlation, Standards, and New Techniques" April 2001. IEEE Transactions on Device and Materials Reliability. Vol 24, No. 2; pgs 99-108.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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